

PTO/SB/08A (04-03)

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		Application Number	
		Filing Date	
		First Named Inventor	Bing Lu et al.
		Group Art Unit	
Examiner Name			
Sheet	1	of	1
		Attorney Docket Number	SC12878TP

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number Number - Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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Examine Initials*	Cite No. ¹	Foreign Patent Document Country Code ³ Number ⁴ Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁵
	AF	PCT WO 02/073682 A1	09-19-2002	BAIER		

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	AG	LERCEL et al., "Etching Processes and Characteristics for the Fabrication of Refractory X-ray Masks," 1998 American Vacuum Society, J. Vac. Sci. Technol. B 16(6), Nov/Dec 1998, pp. 3577-3581.	
	AH	BROOKS et al., "Characterization of Oxynitride Hardmask Removal Processes for Refractory X-ray Mask Fabrication," SPIE Vol. 3331, pp. 255-260 (1998).	
	AI	DAUKSHER et al., "Uniform Low Stress Oxynitride Films for Application as Hardmasks on X-ray Masks," 1997 American Vacuum Society, J. Vac. Sci. Technol. B 15(6), Nov/Dec 1997, pp. 2232-2237.	

Examiner Signature		Date Considered	7-25-05
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